

VARIABLE SURFACE HOT PLATE FOR IMPROVED BAKE UNIFORMITY  
OF SUBSTRATES

ABSTRACT OF THE DISCLOSURE

5 A system, method and apparatus are described for  
improving critical dimension uniformity in baked  
substrates. The system, method and apparatus provide for  
varying the distance between a substrate to be baked and  
the surface of a hot plate such that an approximately  
uniform temperature is obtained in the substrate during  
baking. In one embodiment, the substrate is positioned on  
a hot plate having a recess generally centered on its top  
10 side. The differences in distance between the edges of  
the substrates contacting the hot plate and the distance  
between the center region of the substrate and the bottom  
of the recess enable a generally uniform temperature to  
be obtained in the substrate.